

You are cordially invited to attend the following talks involving Nova technology and customer collaboration:

**SPIE.** ADVANCED LITHOGRAPHY

## CONFERENCE 10585

### Metrology, Inspection, and Process Control for Microlithography XXXII

FEBRUARY  
**26**  
MONDAY

**Scatterometry for gate all around (GAA) technology enablement [10585-4]**

Speaker: Roy Koret, Nova Measuring Instruments Ltd. (Israel)  
**2:10 PM SESSION 2** (Optical Metrology)

FEBRUARY  
**27**  
TUESDAY

**Scatterometry and x-ray metrology for in-line control of spin-transfer torque magnetic random access memory (STT-MRAM) devices [10585-118]**

Speaker: Davide Crotti, IMEC (Belgium)  
**11:10 AM SESSION 5** (Challenges and New Methods)

FEBRUARY  
**28**  
WEDNESDAY

**Implementation of machine learning for high volume manufacturing metrology challenges [10585-32]**

Speaker: Padraig R. Timoney, GLOBALFOUNDRIES (USA)  
**8:20 AM SESSION 8** (Hybrid Metrology & Machine Learning)

FEBRUARY  
**28**  
WEDNESDAY

**Novel hybrid metrology for process integration of gate all around (GAA) devices [10585-34]**

Speaker: Raja Muthinti, IBM Research, Albany NanoTech, NY (USA)  
**9:00 AM SESSION 8** (Hybrid Metrology & Machine Learning)

FEBRUARY  
**28**  
WEDNESDAY

**In-line characterization of non-selective SiGe nodule defects with scatterometry enabled by machine learning [10585-35]**

Speaker: Dexin Kong, IBM Research, Albany NanoTech, NY (USA)  
**9:20 AM SESSION 8** (Hybrid Metrology & Machine Learning)

FEBRUARY  
**28**  
WEDNESDAY

**Lines roughness holistic metrology sensitivity study supported by EUV mask designed with induced roughness [10585-36]**

Speaker: Shimon Levi, Applied Materials Ltd. (Israel)  
**9:40 AM SESSION 8** (Hybrid Metrology & Machine Learning)

FEBRUARY  
**28**  
WEDNESDAY

**Selectivity process control using in-line XPS for self-assembly monolayer-based selective deposition process [10585-38]**

Speaker: Silvia Armini, IMEC (Belgium)  
**10:50 AM SESSION 9** (New Methods and Machine Learning)

FEBRUARY  
**28**  
WEDNESDAY

**Context-based virtual metrology [10585-39]**

Speaker: Peter Ebersbach, GLOBALFOUNDRIES (Germany)  
**11:10 AM SESSION 9** (New Methods and Machine Learning)

## SHORT COURSE

FEBRUARY  
**25**  
SUNDAY

**Scatterometry in Profile, Overlay and Focus Process Control [SC1100]**

Instructors: Hugo Cramer, ASML Netherlands B.V. (Netherlands);  
Igor Turovets, Nova Measuring Instruments Ltd. (Israel)  
**1:30 PM - 5:30 PM**